JOB 3: Job Market III

Time: Thursday 13:30–14:30 Location: P 106

Invited Talk JOB 3.1 Thu 13:30 P 106

TRUMPF SE & Co. KG: Powering EUV Lithography: Inside the Drive Laser Source — •Markus Müller — TRUMPF SE & Co. KG

Extreme-ultraviolet (EUV) lithography is a cornerstone of modern semiconductor fabrication. The TRUMPF high-power Drive Laser is one of the critical elements required to generate EUV radiation. This talk briefly introduces EUV lithography and then focuses on the TRUMPF high-power Drive Laser: its key components, operating principles, and role in reliable EUV light generation.